

## REMARKS

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Applicants respectfully request that the Amendment and Response to Final Office Action be admitted under 37 C.F.R. 1.116. Applicants submit that this amendment presents claims in better form for consideration on appeal. Furthermore, applicants believe that consideration of this amendment could lead to favorable action that would remove one or more issues for appeal. Applicants submit that thus there is good and sufficient reason why this amendment should be admitted now. Reconsideration of this application, as amended, is respectfully requested.

Claims 63-90 are pending. Claims 63-90 stand rejected.

Claims 63 and 76 have been amended. Claims 77-90 have been cancelled. Support for the amendments is found in the specification, the drawings, and in the claims as originally filed. Applicants submit that the amendments do not add new matter.

**Rejections Under 35 U.S.C. § 102(e)**

Claims 63-75 and 77-89 stand rejected under 35 U.S.C. § 102(e) as being anticipated by U.S. Patent No. 6,063,681 of Son ("Son"). The Examiner stated that

With regard to Claim 63, Son teaches a substrate (21), a gate electrode (25) formed over the substrate and defining an underlying channel region in the substrate, said gate electrode having a barrier layer (26) formed on a sidewall of the gate electrode to prohibit silicidation of the sidewall, a source/drain extension

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